

TSMC-02-110



April 16, 2004

To: Commissioner for Patents  
P.O.Box 1450  
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572  
28 Davis Avenue  
Poughkeepsie, N.Y. 12603

Subject: | Serial No. 10/802,564 03/17/04 |

Chun-Chieh Lin et al.

A METHOD OF FORMING DRAM CAPACITORS  
WITH PROTECTED OUTSIDE CROWN SURFACE  
FOR MORE ROBUST STRUCTURES

#### INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation  
In An Application.

The following Patents and/or Publications are submitted to  
comply with the duty of disclosure under CFR 1.97-1.99 and  
37 CFR 1.56.

#### CERTIFICATE OF MAILING

I hereby certify that this correspondence is being  
deposited with the United States Postal Service as first class  
mail in an envelope addressed to: Commissioner for Patents,  
P.O. Box 1450, Alexandria, VA 22313-1450, on April 26, 2004.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

Stephen B. Ackerman 4/26/04

The following two U.S. Patents both describe a method for fabricating a crown capacitor having double sidewalls using a freestanding bottom electrode:

- 1) U.S. Patent 6,130,128 to Lin, "Method of Fabricating Crown Capacitor."
- 2) U.S. Patent 6,187,625 to Lin et al., "Method of Fabricating Crown Capacitor."

U.S. Patent 6,180,483 to Linliu, "Structure and Fabrication Method for Multiple Crown Capacitor," describes a method for making multiple crown capacitors.

U.S. Patent 6,187,624 to Huang, "Method for Making Closely Spaced Capacitors with Reduced Parasitic Capacitance on a Dynamic Random Access Memory (DRAM) Device," describes a method for making closely spaced capacitors in adjacent recesses.

Sincerely,



Stephen B. Ackerman,  
Reg. No. 37761

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APR 29 2004

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Chun-Chieh Lin et al

Filing Date

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## U. S. PATENT DOCUMENTS

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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.